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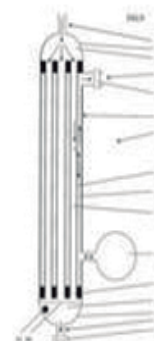
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Title: FILTRATION PROCESS USING MICROPOROUS FILTER WITH A LOW ELUTION ANTIMICROBIAL SOURCE

Abstract: A method for filtration of fluid, primarily liquid, with fluid filtration device having a fluid inlet and a fluid outlet and a fluid path between the inlet and the outlet through a microporous filter with a pore size adapted for filtering bacteria or bacteria and virus by mechanical particle size separation. The filtration device comprises further an antimicrobial source adding antimicrobial substance to the fluid in the fluid path between the fluid inlet and the inlet surface of the microporous filter. The fluid filtration device is provided with a design flow through the device, the design flow assuring a proper filtration of the fluid flowing through the device with a cleaned fluid at the flow outlet. The antimicrobial source, for example a halogen source, is configured to release the antimicrobial substance at a low elution rate that is not high enough for killing substantially all the microbes in the fluid during the time it takes the fluid to flow through the device at the design flow, but which is high enough for prevention of a biofilm in the long term.



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